

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|-------|---|--|------------------|---------|------------------|
| L2 | 1 | (wafer or semiconductor or substrate or workpiece) and (motor or drive) same ("ball guide" and "ball screw" and "ball block") | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 10:03 |
| L3 | 3 | (wafer or semiconductor or substrate or workpiece) and (motor or drive) and ("ball guide" and "ball screw" and "ball block") | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 09:59 |
| L4 | 3 | (motor or drive) and ("ball guide" and "ball screw" and "ball block") | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 09:59 |
| L5 | 3 | (wafer or semiconductor or substrate or workpiece) and (motor or drive) same ("ball screw" and "ball block") | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 10:04 |
| L6 | 10803 | (wafer or semiconductor or substrate or workpiece) and (motor or drive) same (screw and block) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 10:05 |
| L7 | 928 | (wafer or semiconductor or substrate or workpiece) and (motor or drive) near10 (screw near10 block) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 10:05 |
| L8 | 17 | (wafer or semiconductor or substrate or workpiece) and (motor or drive) near10 (screw near10 block) and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 10:10 |
| L9 | 196 | (wafer or semiconductor or substrate or workpiece) same (motor or drive) near10 (screw near10 block) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 10:10 |

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| L25 | 1 | "2002281628" | JPO | OR | ON | 2006/09/29 14:42 |
| S1 | 181 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (holder or support) near10 (groove or drain\$3) | US-PGPUB; USPAT | OR | ON | 2006/09/21 11:55 |
| S2 | 249 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (holder or support) near10 (groove or drain\$3 or hole) | US-PGPUB; USPAT | OR | ON | 2006/05/18 19:11 |
| S3 | 29 | "6115867" "6148463" "6357457" | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:13 |
| S4 | 16146 | (wafer or semiconductor or substrate or workpiece) and plate near10 (nozzle or spray\$3) | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:14 |
| S5 | 381 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) and plate near10 (nozzle or spray\$3) | US-PGPUB; USPAT | OR | ON | 2006/09/28 17:26 |
| S6 | 217 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same plate near10 (nozzle or spray\$3) | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:15 |
| S7 | 27 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same plate near10 (nozzle or spray\$3) near10 (plurality or array or group or multiple) | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:28 |
| S8 | 0 | (wafer or semiconductor or substrate or workpiece) same plate near10 (nozzle or spray\$3) near10 (plurality or array or group or multiple) near10 ((top and bottom) or (above and below) or (first near5 surface and second near5 surface)) near15 (gas and liquid) and (nozzle or spray) near10 (slant\$3 or inclin\$3 or slop\$3) and (motor or driv\$3) near10 (rotat\$3 and (hold\$3 or arm)) | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:35 |

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| S9 | 0 | (wafer or semiconductor or substrate or workpiece) same plate near10 (nozzle or spray\$3) near10 (plurality or array or group or multiple) near15 (gas and liquid) and (nozzle or spray) near10 (slant\$3 or inclin\$3 or slop\$3) and (motor or driv\$3) near10 (rotat\$3 and (hold\$3 or arm)) | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:35 |
| S10 | 0 | (wafer or semiconductor or substrate or workpiece) same plate near10 (nozzle or spray\$3) near10 (plurality or array or group or multiple) near15 (gas and liquid) and (motor or driv\$3) near10 (rotat\$3 and (hold\$3 or arm)) | US-PGPUB; USPAT | OR | ON | 2006/09/28 17:49 |
| S11 | 7 | (wafer or semiconductor or substrate or workpiece) same (nozzle or spray\$3) near10 (plurality or array or group or multiple) near15 (gas and liquid) and (motor or driv\$3) near10 (rotat\$3 and (hold\$3 or arm)) | US-PGPUB; USPAT | OR | ON | 2006/06/21 17:06 |
| S12 | 13 | (wafer or semiconductor or substrate or workpiece) same (nozzle or spray\$3) near10 (plat\$3) near15 (gas and liquid) and (motor or driv\$3) near10 (rotat\$3 and (hold\$3 or arm)) | US-PGPUB; USPAT | OR | ON | 2006/05/19 09:55 |
| S13 | 6 | (wafer or semiconductor or substrate or workpiece) same (nozzle or spray\$3) near10 (plat\$3) near15 (gas and liquid) same ((top near10 bottom) or (above near10 below) or (upper near10 lower)) | US-PGPUB; USPAT | OR | ON | 2006/05/19 10:16 |
| S14 | 592 | (wafer or semiconductor or substrate or workpiece) same (nozzle or spray\$3) near10 (plat\$3) same ((top near10 bottom) or (above near10 below) or (upper near10 lower)) | US-PGPUB; USPAT | OR | ON | 2006/09/28 17:49 |
| S15 | 274 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same (nozzle or spray\$3) near10 (plat\$3) | US-PGPUB; USPAT | OR | ON | 2006/05/19 11:54 |
| S16 | 0 | 104/902.ccls. | US-PGPUB; USPAT | OR | ON | 2006/06/21 17:06 |

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| S17 | 1865 | 134/902.ccls. | US-PGPUB; USPAT | OR | ON | 2006/06/21 17:06 |
| S18 | 1218 | S17 and (nozzle or spray\$3) | US-PGPUB; USPAT | OR | ON | 2006/06/21 17:06 |
| S19 | 335 | S18 and (134/151,153,198.ccls.) | US-PGPUB; USPAT | OR | ON | 2006/06/21 17:12 |
| S20 | 3 | US-6115867-\$.DID. OR US-6148463-\$.DID. OR US-6357457-\$.DID. | US-PGPUB; USPAT | OR | ON | 2006/09/28 18:01 |
| S21 | 42 | "5248380" | US-PGPUB; USPAT | OR | ON | 2006/09/21 16:51 |
| S22 | 55 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) and plate near10 (nozzle or spray\$3) near10 (plurality or multiple or several) | US-PGPUB; USPAT | OR | ON | 2006/09/28 17:26 |
| S23 | 31 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same plate near10 (nozzle or spray\$3) near10 (plurality or multiple or several) | US-PGPUB; USPAT | OR | ON | 2006/09/28 17:26 |
| S24 | 26 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same (nozzle or spray\$3) near10 (plat\$3) same ((top near10 bottom) or (above near10 below) or (upper near10 lower)) | US-PGPUB; USPAT | OR | ON | 2006/09/28 17:50 |
| S25 | 29 | plurality near5 nozzle near10 peripheral and "134"/\$.ccls. | US-PGPUB; USPAT | OR | ON | 2006/09/28 18:02 |
| S26 | 1467 | nozzle near10 center and nozzle near10 (edge or periph\$3) | US-PGPUB | OR | ON | 2006/09/28 18:03 |
| S27 | 98 | nozzle near10 center and nozzle near10 (edge or periph\$3) and "134"/\$.ccls. | US-PGPUB | OR | ON | 2006/09/28 18:08 |
| S28 | 389 | "134"/\$.ccls. and plurality near6 nozzle | US-PGPUB | OR | ON | 2006/09/28 18:08 |
| S29 | 201 | "134"/\$.ccls. and plurality near6 nozzle and (wafer or semiconductor or substrate) | US-PGPUB | OR | ON | 2006/09/28 18:25 |
| S30 | 0 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same nozzle near10 (diameter) near8 (decreas\$3 or smaller or smaller) near10 (peripher\$3 or outer or edge) | US-PGPUB | OR | ON | 2006/09/28 18:30 |

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| S31 | 25 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) and nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) | US-PGPUB | OR | ON | 2006/09/28 18:31 |
| S32 | 17 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) | US-PGPUB | OR | ON | 2006/09/28 18:42 |
| S33 | 235 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) | US-PGPUB | OR | ON | 2006/09/28 18:42 |
| S34 | 19 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) near10 (edge or periphery or outer or peripher\$3 or outside) | US-PGPUB | OR | ON | 2006/09/28 18:42 |
| S35 | 785 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 18:42 |
| S36 | 102 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) near10 (edge or periphery or outer or peripher\$3 or outside) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 19:16 |
| S37 | 52 | "134"/\$.ccls. and (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 19:16 |
| S38 | 197 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (decreas\$3 or smaller or smaller or increas\$3 or larger) near10 (edge or periphery or outer or peripher\$3 or outside) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 19:33 |

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| S39 | 1005 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (increas\$3 or larger) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 19:33 |
| S40 | 64 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (increas\$3 or larger) and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 20:04 |
| S41 | 32 | (wafer or semiconductor or substrate or workpiece) same nozzle same (diameter) near8 (increas\$3 or larger) and "134"/902.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 19:33 |
| S42 | 361 | (wafer or semiconductor or substrate or workpiece) same nozzle near10 (angle or inclin\$4 or tilt\$3 or slant\$3 or declin\$4) and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 20:07 |
| S43 | 144 | (wafer or semiconductor or substrate or workpiece) same nozzle near10 (gas) near10 (plurality or several or multiple) and nozzle near10 (liquid or fluid or chemical) near10 (plurality or several or multiple) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 20:10 |
| S44 | 105 | (wafer or semiconductor or substrate or workpiece) same nozzle near10 (gas) near10 (top or front) and nozzle near10 (gas) near10 (back or bottom) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 20:30 |
| S45 | 8 | "6874516" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/28 20:22 |
| S46 | 114 | (wafer or semiconductor or substrate or workpiece) same plate near10 (bottom or below or base or lower) near10 (rotat\$3) near10 (motor or drive) and plate near10 (top or above or upper) near10 (rotat\$3) near10 (drive or motor) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT | OR | ON | 2006/09/29 09:53 |